

Piranha Chemical Bench

Operating Procedures LINK



Process Description:

During wafer fabrication it is necessary to perform cleaning sequences. Wafer cleaning removes organics, particulates, surface oxide, surface ions, and metal contaminants. Cleaning can be a multi-step process involving acids and bases. Piranha clean is one widely used process. A Piranha clean is comprised of hot sulfuric acid and hydrogen peroxide and is effective against organic contaminants.

Equipment Description:

The Piranha chemical bench has one process tank prepared with sulfuric acid. The bench is equipped with two wafer holders and one holder for wafer pieces, one quick dump rinse tank (QDR), a hotplate and sink. The process tank has level sensor, temperature control and timer.

<i>Materials Allowed</i>		<i>Materials Not Allowed</i>
Silicon		Glass
Silicon dioxide		III-V semiconductors
Silicon nitride		Metals
Quartz		
Photoresists		